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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Application of :
Yasuhiko SUGIYAMA et al. :
Serial No. 10/721,522 : Group Art Unit - 1756
Filed: November 24, 2003 : Examiner: Stephen D. Rosasco
For: PHOTOMASK CORRECTION :
METHOD USING COMPOS- :
ITE CHARGED PARTICLE :
BEAM, AND DEVICE USED :
IN THE CORRECTION :
METHOD : Docket No. S004-5168

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MS FEE AMENDMENT
COMMISSIONER FOR PATENTS
P.O. BOX 1450
ALEXANDRIA, VA 22313-1450

RESPONSE

S I R:

In response to the Office Action dated September 26, 2005, applicants amend their application as follows:

ELECTION OF INVENTION:

Applicants provisionally elect, with traverse, the invention characterized by the Examiner as Group I drawn to a method for correcting a mask, and submit that claims 1-6 are readable on the elected invention.